## Amendments to and listing of the claims:

Please amend claim 1 so that the claims read as follows:

- 1. (Currently Amended) A resin composition for stereolithography, which is an actinic radiation-curable resin composition comprising:
- a cationic-polymerizable organic compound;
- a radical-polymerizable organic compound;
- a photo initiator for cationic polymerization; and
- an ultraviolet light-sensitive photo initiator for radical polymerization,

wherein the photo initiator for cationic polymerization comprises a compound represented by the following formula (I), the compound having a purity of 97% or higher and containing less than 3% by mass of a compound represented by the following formula (II):

wherein M represents an antimony atom or a phosphorus atom; and the broken line between  $S^+$  and  $MF_6^-$  represents an ionic bond.

2. (Canceled)

- 3. (Previously Presented) The resin composition for stereolithography as claimed in claim 1, wherein M in the compound represented by the formula (I) is an antimony atom.
  - 4. (Canceled)
- 5. (Previously Presented) The resin composition for stereolithography as claimed in claim 1, wherein the cationic-polymerizable organic compound comprises at least one compound having an epoxy group.
- 6. (Previously Presented) The resin composition for stereolithography as claimed in claim 1, wherein the radical-polymerizable organic compound comprises at least one compound having a (meth)acryl group.
- 7. (Previously Presented) The resin composition for stereolithography as claimed in claim 1, which comprises an oxetane compound at a ratio of from 1 to 30% by mass with respect to the mass of the cationic-polymerizable organic compound.
- 8. (Previously Presented) The resin composition for stereolithography as claimed in claim 1, which comprises a polyalkylene ether compound at a ratio of from 1 to 30% by mass with respect to the mass of the cationic-polymerizable organic compound.
- 9. (Previously Presented) The resin composition for stereolithography as claimed in claim 1, wherein a concentration of diphenyl sulfoxide in the compound represented by formula (I) is less than 0.05% by mass.
- 10. (Previously Presented) The resin composition for stereolithography as claimed in claim 1, wherein the photoinitiator for cationic polymerization contains substantially no compound represented by formula (II).